



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor

Kaichiro NAKANO, et al.

Serial No.

09/036,219

Filed

March 6, 1998

Title

CHEMICALLY AMPLIFIED RESIST LARGE IN

TRANSPARENCY AND SENSITIVITY TO EXPOSURE LIGHT LESS THAN 248 NANOMETER WAVELENGTH AND

PROCESS OF FORMING MASK

April 23, 198

Assistant Commissioner for Patents Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT

S I R:

In order to comply with discretionary rules 37 CFR 1.97 and 1.98, attached hereto is a copy of Form PTO-1449 and copies of the documents listed thereon. These documents contain information which the Examiner may consider to be important in deciding whether to issue a patent in the instant application.

As this Statement is being filed prior to issuance of a first Office Action, no fee is due.

As two of these documents are written in a language other than English, English language abstracts are annexed thereto explaining their relevancy in accordance with 37 CFR §1.98(a)(3).

The present Disclosure Statement is being submitted in compliance with 37 CFR 1.56 as an Examiner might consider any cited document important in deciding whether to allow the application to issue as a patent, but the citation of each

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Early and favorable consideration is respectfully solicited.

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Respectfully submitted,

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HELFGOTT & KARAS, P.C. EMPIRE STATE BUILDING 60TH FLOOR NEW YORK, NEW YORK 10118 (212) 643-5000 DOCKET NO.: NEKW 14.868 SH:ddh:14868ids

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: Kaichiro NAKANO

Filed

: Concurrently herewith

For

: CHEMICALLY AMPLIFIED RESIST LARGE IN TRANSPARENCY AND

SENSITIVITY TO EXPOSURE LIGHT LESS THAN 248 NANOMETER

WAVELENGTH AND PROCESS OF FORMING MASK

Serial No.: Concurrently herewith

Hon. Commissioner of Patents and Trademarks Washington, D.C. 20231 #2 A. Gassavary 6-26-98

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